

Title (en)

OPTICAL SUBSTRATE, SEMICONDUCTOR LIGHT-EMITTING ELEMENT AND METHOD OF MANUFACTURING SEMICONDUCTOR LIGHT-EMITTING ELEMENT

Title (de)

OPTISCHES SUBSTRAT, LICHTEMITTIERENDES HALBLEITERELEMENT UND VERFAHREN ZUR HERSTELLUNG DES LICHTEMITTIERENDEN HALBLEITERELEMENTS

Title (fr)

SUBSTRAT OPTIQUE, ÉLÉMENT ÉLECTROLUMINESCENT SEMI-CONDUCTEUR ET PROCÉDÉ DE FABRICATION D'ÉLÉMENT ÉLECTROLUMINESCENT SEMI-CONDUCTEUR

Publication

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Application

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- JP 2012103489 A 20120427
- JP 2012103490 A 20120427
- JP 2012227295 A 20121012
- JP 2012267377 A 20121206
- JP 2012267488 A 20121206
- JP 2012280241 A 20121221
- EP 13771897 A 20130329

Abstract (en)

An optical substrate that includes a substrate and a concave-convex structure which is formed in a part or a whole of a surface of the substrate, wherein at least one part of the concave-convex structure includes a plurality of convex portions arranged apart from each other; at least one of the plurality of convex portions is a unique convex portion that includes one or more convex members or concave members in a surface and an average interval Pave in the concave-convex structure is equal to or more than 1.5 µm but equal to or less than 10 µm. When the optical substrate is used in a semiconductor light-emitting element, dislocations in a semiconductor layer are dispersed to reduce the dislocation density, and thus internal quantum efficiency IQE is improved, and a waveguide mode is removed by light scattering and thus the light extraction efficiency LEE is increased, with the result that the efficiency of light emission of the semiconductor light-emitting element is enhanced.

IPC 8 full level

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Citation (applicant)

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Citation (search report)

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IN 1916MUN2014 A 20150710; JP 6235459 B2 20171122; JP WO2013150984 A1 20151217; KR 101763460 B1 20170731;
KR 101862500 B1 20180529; KR 20140133867 A 20141120; KR 20160148052 A 20161223; RU 2014144362 A 20160527;
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